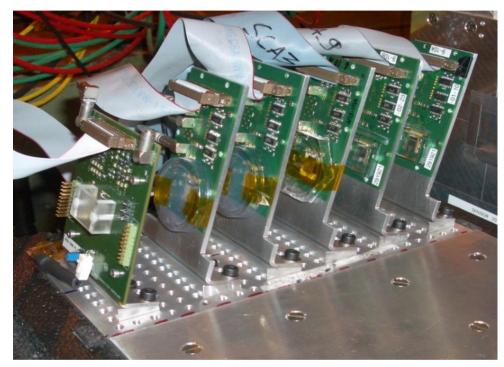
Characterization and beam tests of Barcelona FE-I3 planar n-in-p and 3D double sided devices



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Layout

This talk will consist of four parts:

- Brief introduction
 - Sensor technologies.
 - > Description of the FE-I3 read-out chip.
- Characterization
 - > Results from the characterization in laboratory at IFAE.
- Test beam studies
 - Results and interpretation of the beam test studies.
- Conclusions

Introduction to CNM FE-I3 devices

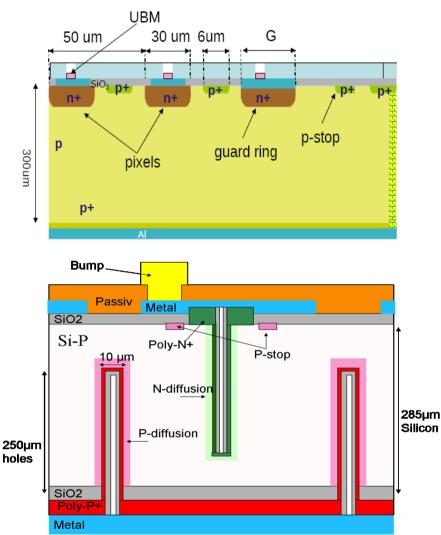
• Planar n-in-p

- Planar n⁺ in p sensors in a 300 µm deep substrate.
- > No bias grid present in CNM devices.
- > p-stop isolation, 11 guard ring design.
- 3D double sided
 - Electrodes etched into the bulk, perpendicular to the wafer's surface.
 - Double sided: columns etched from opposite sides of the wafer for each electrode type.
 - Columns are 250 µm deep in a 300 µm thick p-substrate.

Nomenclature

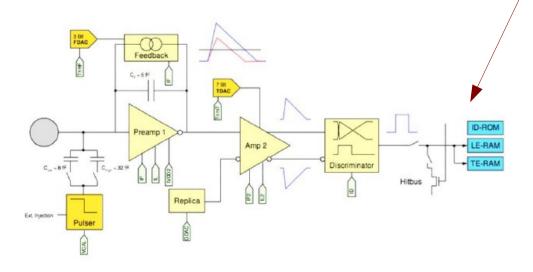
The nomenclature used for the devices is:

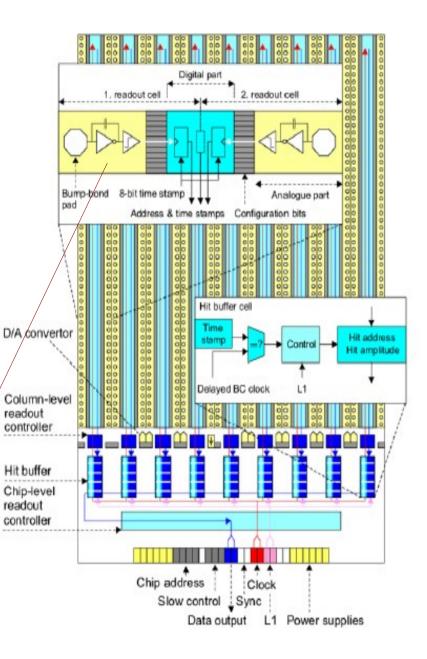
(Mounting)_(production)_(type)_(number), i.e. BCN_CNM_PL_04



Readout chip

- The pixel sensors studied are bump-bonded at Barcelona on the FE-I3 readout chip (currently used in ATLAS).
- 2880 cells of 400 x 50 µm² size, arranged in 160x18 matrix (same as sensors).
- Both the threshold and the Time over Threshold (ToT, related to the charge deposited in a pixel) can be tuned by varying DAC values.
 - In all the characterized devices, the tuning is: 30 ToT units = 20.10³e⁻.



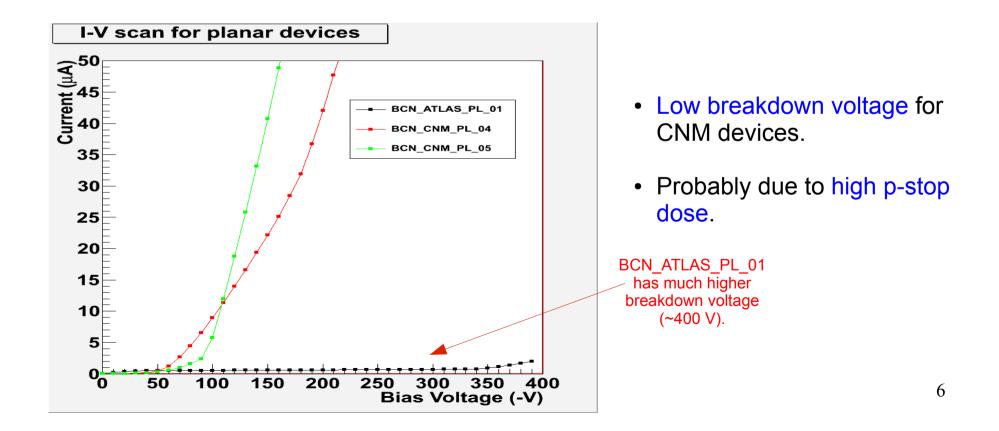


Characterization



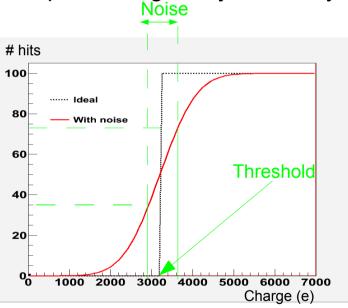
Planar n-in-p (1)

- First step in characterization procedure: IV measurement.
- Results for BCN_CNM_PL_04 and 05 are shown and compared to BCN_ATLAS_PL_01 (n-on-n).
- Breakdown voltage around -100V for the CNM devices, full depletion around -65 V (measured at CNM).



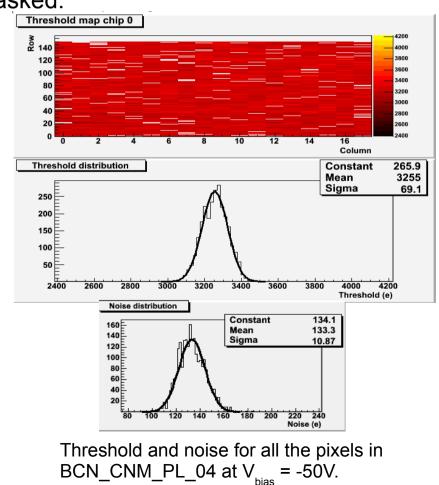
Planar n-in-p (2)

- Threshold scan: Different amount of charge injected into each pixel, 100 times.
- Threshold for each pixel set at 3200 e⁻.
- The top rows both for planar and 3D are floating (not connected), to simplify the processing. They will always appear masked.



Expected curve shape for each pixel

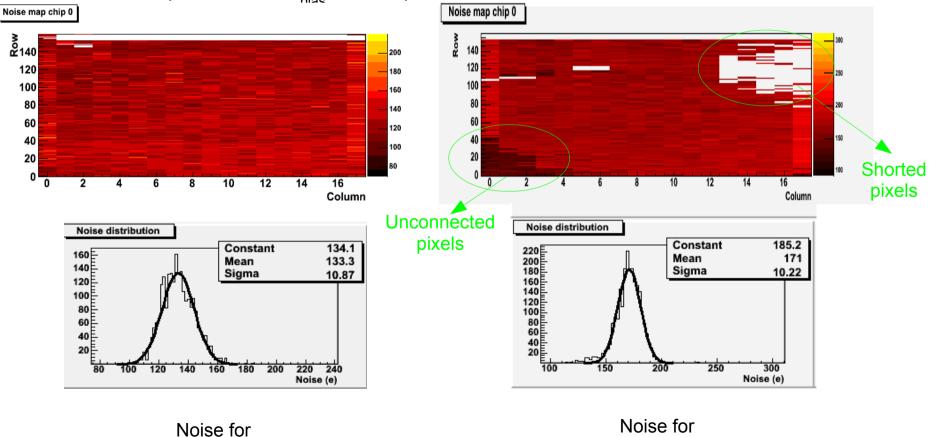
 The threshold has been adjusted successfully for CNM planar n-inp devices



Planar n-in-p (3)

BCN_CNM_PL_04 at V_{bias} = -50V.

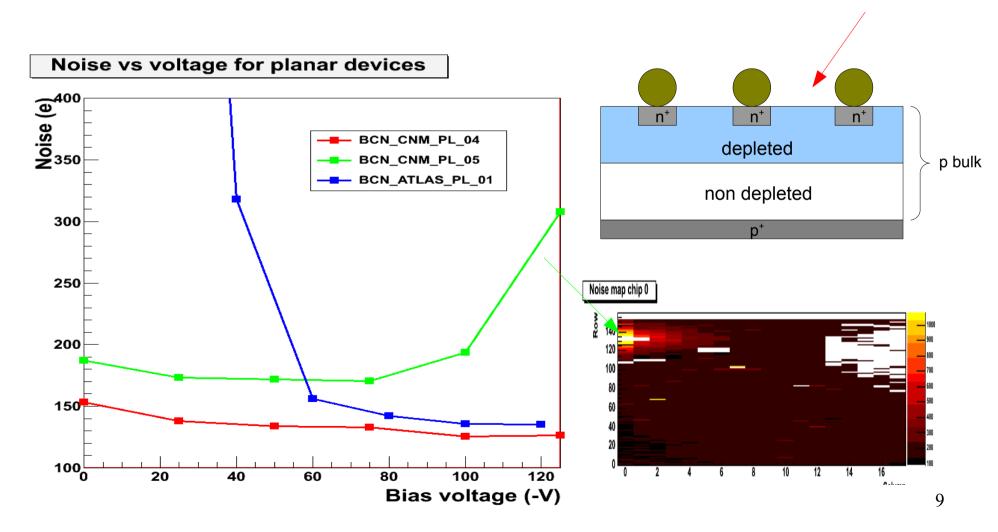
- Noise measurement: Different observations can be made:
 - BCN_CNM_PL_04: All pixels OK (~140 e⁻ at V_{bias} = -50 V).
 - BCN_CNM_PL_05: Found shorted and unconnected pixels. Central pixels OK (~170 e⁻ at V_{bias} = -50V).



BCN_CNM_PL_05 at V_{bias} = -50V.

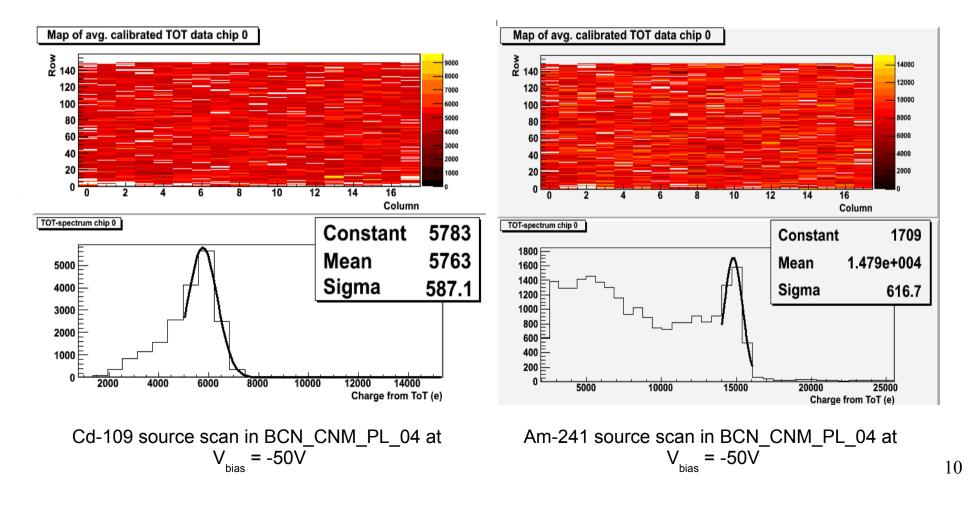
Planar n-in-p (4)

- "Hot" noisy spot in BCN_CNM_PL_05 appears for V < -95 V.
- N-in-p have low noise for V < $V_{depletion} \rightarrow$ Depletion region grows from the pixel.



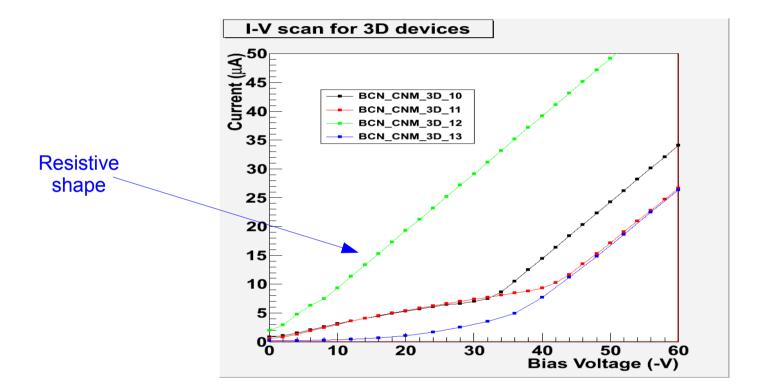
Planar n-in-p (5)

- To see that the devices work, check that they collect charge.
- Source scan with Cd-109 (21.4 KeV photons) and Am-241 (60 KeV photons).
- Found a peak around 6000 e⁻ (Cd-109) and 15000 e⁻ (Am-241), as expected.



3D devices (1)

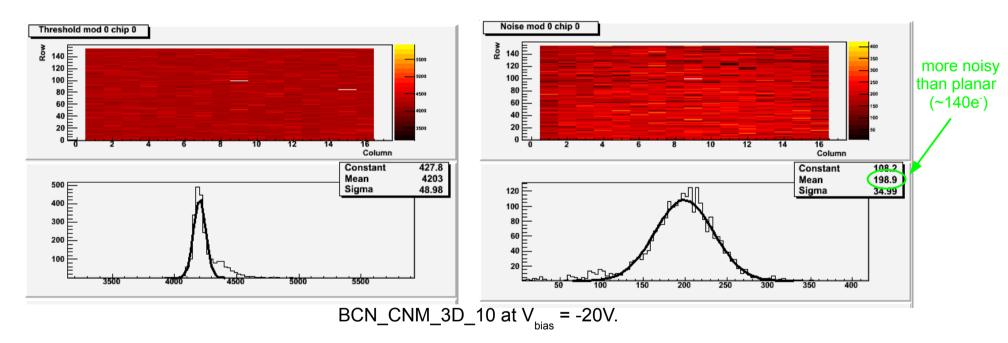
IV scan shows a low breakdown voltage (~ 35 V).



• BCN_CNM_3D_12 has a resistive shape. We are investigating this device.

3D devices (2)

• Threshold for each pixel set higher than for planars: ~4000 e⁻.



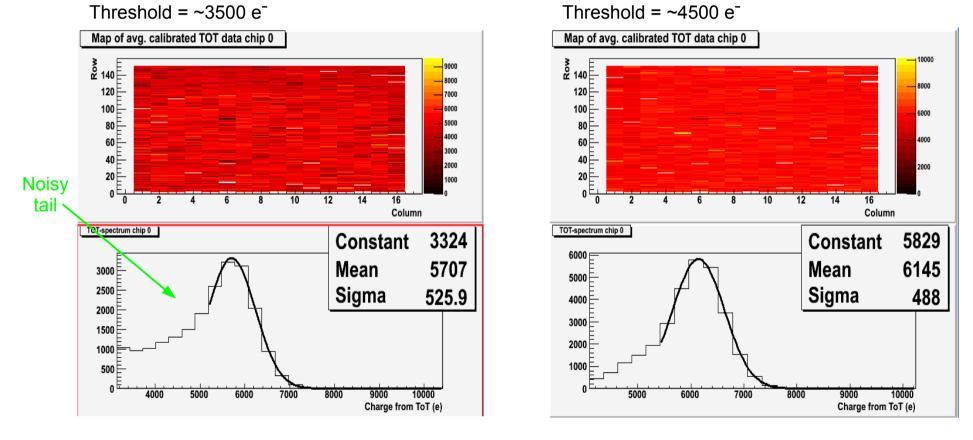
Threshold

Noise

- All 3D devices are found to be noisy $(200 400 e^{-})$.
- The production run was problematic; also high p-stop might cause microdischarges.

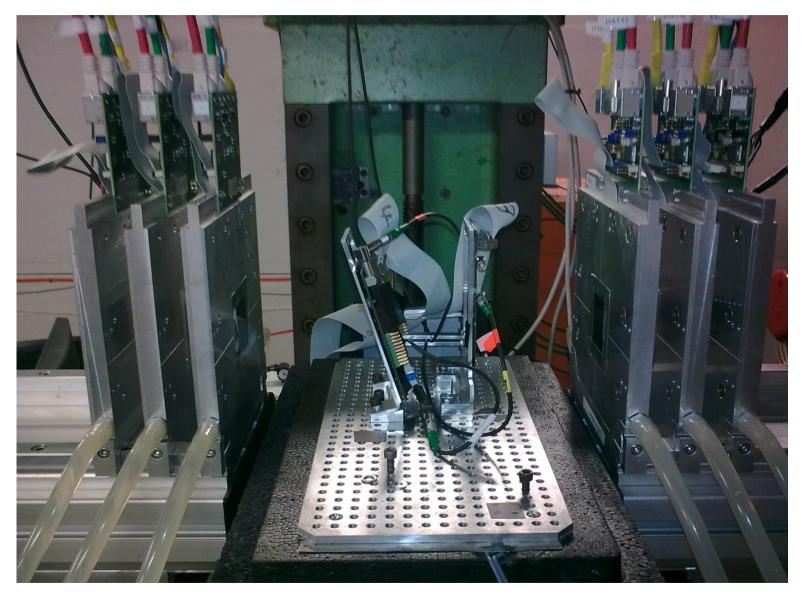
3D devices (3)

- Source scan for Cd-109 shows similar results than for planar devices. Verified charge collection although the devices are noisy.
- A "noisy tail" appears when "low" thresholds are set.



Source scans with Cd-109 (21.4 KeV) for BCN_CNM_3D_11 at V_{bias} = -20 V

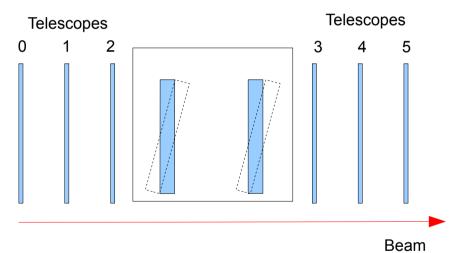
Test Beam studies



3D CNM device at DESY

General information

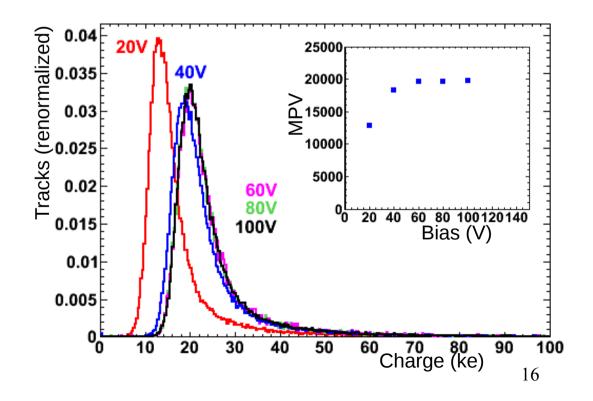
- After characterization in lab, the working devices were brought to different testbeams:
 - > BCN_CNM_PL_04 \rightarrow 2010 July test beam at CERN.
 - > BCN_CNM_PL_05 \rightarrow 2010 October test beam at CERN
 - > BCN_CNM_3D_13 \rightarrow 2011 April test beam at DESY.
- The sensors were placed under a beam with energies:
 - > CERN testbeams \rightarrow 120 GeV charged pions.
 - > DESY testbeam \rightarrow 4 GeV electrons.
- The resolution of the telescopes is:
 - > CERN testbeams \rightarrow few μ m.
 - > DESY testbeam \rightarrow ~ 20 μ m.
- The devices were placed with a normal incidence and with a 15 deg incidence (with respect to the beam axis).
- The results for the BCN_CNM_3D_13 are still PRELIMINARY.



Planar n-in-p (1)

Cluster spectrum with all pixel

- The charge deposit for each reconstructed cluster is plotted.
- The peak is found around $20 \cdot 10^3 e^-$ (as expected, since $dE_{m,i,p}$ /dx ~ 1 MeV)
- For the sensor under depleted, less charge is detected.
- Results are compatible with a depleted sensor at -60 V (as measured by CNM).



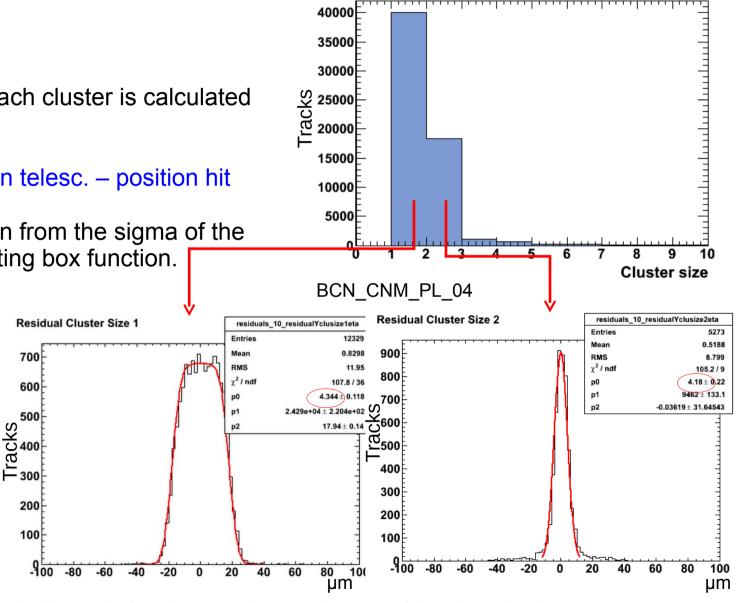
Planar n-in-p (2)

Resolution

The residual for each cluster is calculated • with:

Residual = position telesc. – position hit

Resolution is taken from the sigma of the gaussian in the fitting box function.



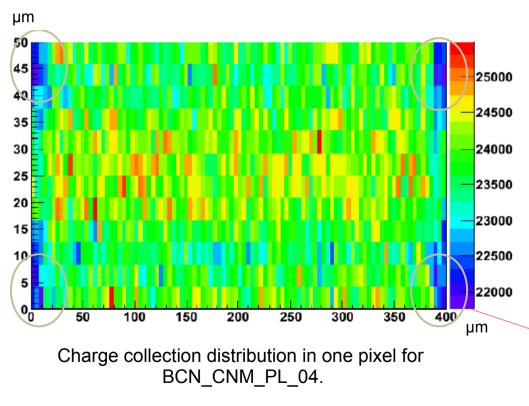
17

Single and double pixel resolution (~ 5μ m), consistent with other devices • (current n-in-n ATLAS sensors).

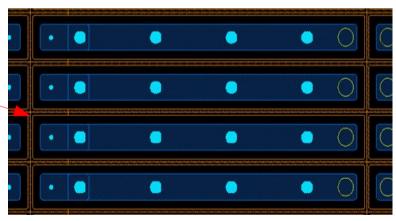
Planar n-in-p (3)

Charge collection

• The position of the collected charge is associated to the track matched to the cluster. Then, summed all pixels.



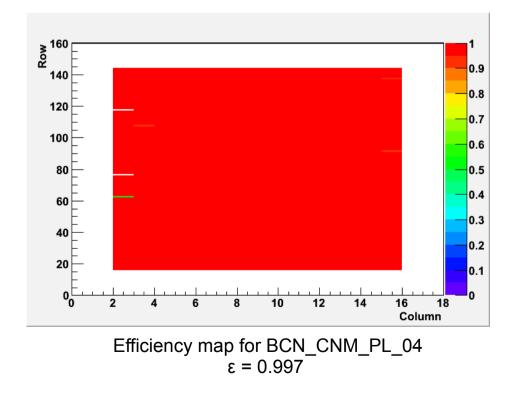
- Low charge deposited in the edges.
- At these points, part of the charge is lost in the space between pixels.



Planar n-in-p (4)

Efficiency map

- The efficiency is calculated for each pixel in the central region: $\epsilon = (N_{hits}) / (N_{tracks matched})$
- The efficiency for BCN_CNM_PL_04 is shown.



Planar n-in-p (5)

Edge Efficiency Fit for DUT 15

200

400

Edge efficiency

Efficiency

0.8

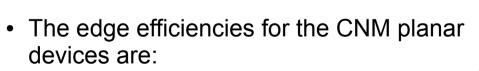
0.6

0.4

0.2

8

The edge efficiency measures the efficiency in the pixels on columns 1, 2, 17 and 18 (1 and 18 have longer pixels: 50 x 600 µm².)



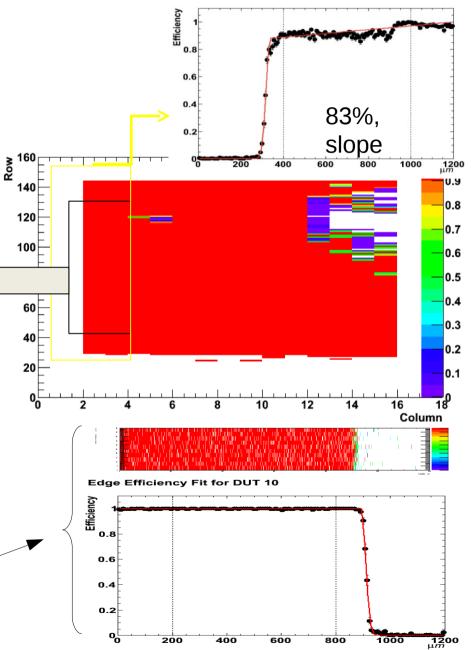
600

800

1000

1200

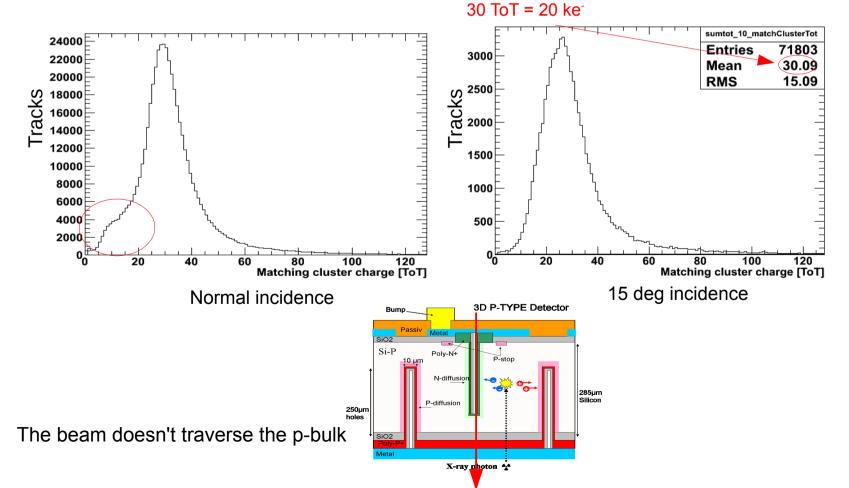
- > BCN_CNM_PL_04: ε = 0.996⁻
- > BCN_CNM_PL_05: ε = 0.999



3D devices (1)

Cluster spectrum with all pixels

- Differences observed between normal and 15 deg incidence:
 - The curve shape for normal incidence is different because of hits in the electrode area.

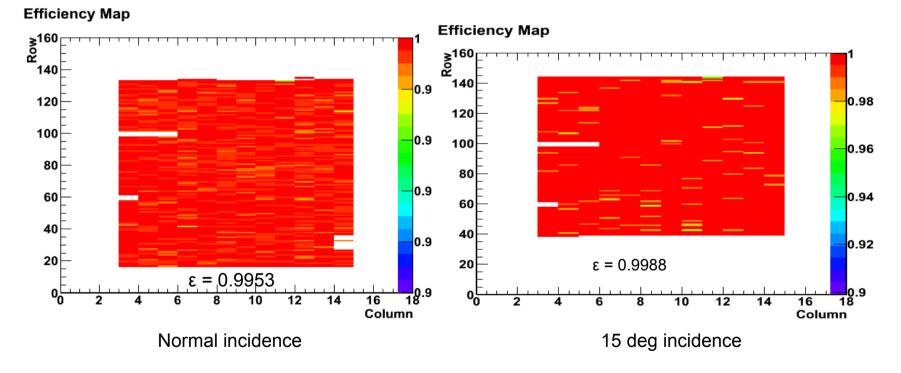


21

3D devices (2)

Efficiency map

The efficiency for BCN_CNM_3D_13 is shown for normal incidence and 15 degrees.



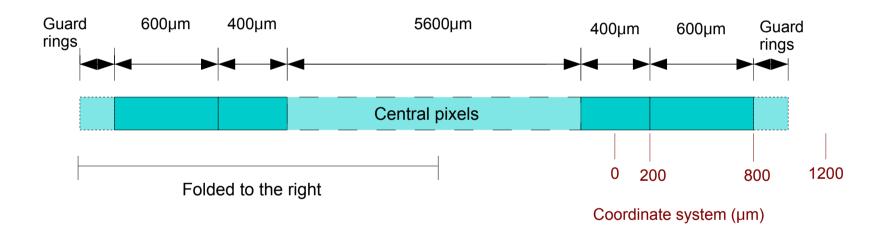
• Lower efficiency under normal incidence: hits in the pixel's column area are lost.

Conclusions

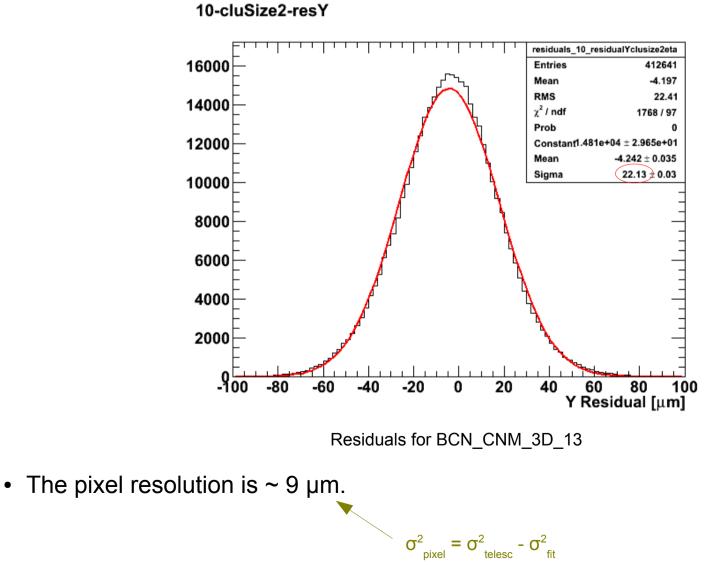
- First FE-I3 production from CNM for n-in-p planar and 3D double sided was tested at IFAE and in test beams.
- The devices were able to detect charge.
- Several issues in the production made these devices not optimal. It translated into low breakdown and noisy pixels. However, the performance in terms of efficiency and resolution is as good as standard devices.
- This problems are **solved** for the new 3D sensors from CNM.
- These productions are an essential step for the ATLAS IBL qualification production. Giulio is going to talk about this in a moment.

Backup slides

Coordinate system for edge efficiency



Residuals for clusters of 2 pixel size for BCN_CNM_3D_13.



26